

US010366855B2

(12) United States Patent

Ogawa

(54) FUSE ELEMENT ASSEMBLIES

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- $(*)$ Notice: Subject to any disclaimer, the term of this patent is extended or adjusted under 35 U.S.C. 154(b) by 0 days. U.S.C. 154(b) by 0 days.

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 $\begin{bmatrix} 21 \end{bmatrix}$ Appl. No.: 15/685,387
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- (22) Filed: **Aug. 24, 2017**

(65) **Prior Publication Data** vol. 23(9), Sep. 2002, p. 523-525.

US 2017/0372861 A1 Dec. 28, 2017

US 2017/0372861 A1

Related U.S. Application Data

- (63) Continuation of application No. $14/847,235$, filed on Sep. 8, 2015, now Pat. No. 9,773,632.
- (51) Int. Cl. $\begin{array}{ll}\nH01H & 85/05 \\
H01H & 85/143\n\end{array}$ (2006.01) HOIH 85/143 (2006.01)
HOIL 23/525 (2006.01) H01L 23/525
- (52) **U.S. Cl.** CPC **HOIH 85/05** (2013.01); **HOIH 85/143** (2013.01); **HOIL 23/5256** (2013.01)
- (2013.01); *HUIL 23/3236* (2013.01)
(58) Field of Classification Search CPC ... H01H 85/05; H01H 85/143; H01L 23/5256 USPC . 337 / 290 See application file for complete search history.

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(10) Patent No.: US $10,366,855$ B2
(45) Date of Patent: Jul. 30, 2019 (45) Date of Patent:

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(57) ABSTRACT

Some embodiments include a fuse element assembly having a first portion configured to rupture as materials of the first The assembly has a second portion configured to accumulate the materials that have flowed from the first portion . The assembly also has a control element configured to divide the flow of materials into at least two paths along the second portion. The first portion may be a fuse-link and the second portion may be a cathode coupled to the fuse-link through a narrow neck region. The control element may be, for (56) **References Cited References Cited References Cited References Ref**

10 Claims, 12 Drawing Sheets

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 $FIG. 4$

 $FIG. 5$

FIG. 7

FIG. 15

FIG. 17

FIG. 19

application Ser. No. $14/847,235$, which was filed Sep. 8, of FIG. 1
2015, and which is hereby incorporated herein by reference. assembly.

may serve numerous functions. For example, E-fuses may
provide overcurrent and/or overvoltage protection. As
into another example embodiment circuit assembly.
another example, E-fuses may be utilized in conjunction
with re

ode when electrical characteristics (e.g., current flow, volt-
age differential, etc.) across the fuse-link exceed a predeter-
into an example embodiment circuit assembly. age differential, etc.) across the fuse-link exceed a predeter-
mined threshold.
FIG. 20 diagrammatically illustrates an example pulse
Problems may occur during operation of E-fuses in that sequence that may be utilized re

material from the fuse-link accumulates at the cathode as the 30 of FIG. 19 to rupture a fuse-link of the fuse element fuse-link is ruptured, and such accumulating material may assembly. fuse cause cracks or other defects to develop in structures adja-

eent the cathode. It would be desirable to develop new DETAILED DESCRIPTION OF THE cent the cathode. It would be desirable to develop new DETAILED DESCRIPTION OF TH
E-fuse configurations which alleviate or prevent such prob-
LLUSTRATED EMBODIMENTS E-fuse configurations which alleviate or prevent such problems. l ems. 35

embodiment fuse element assembly of FIG. 1 incorporated into an example embodiment circuit assembly.

sequence that may be utilized relative to the circuit assembly FIGS **1-20**.
of FIG. **2** to rupture a fuse-link of the fuse element assembly 50 Referring to FIG. **1**, an example embodiment fuse element
FIG. **5** diagrammatic

FIG. 5 diagrammatically illustrates another example pulse sequence that may be utilized relative to the circuit assembly

embodiment fuse element assembly of FIG. 1 incorporated element configuration, the configuration 10 includes a slit 18 into another example embodiment circuit assembly.
extending into the cathode 12.

FIG. 8 is a diagrammatic top view of another example 60 In the illustrated configuration, the cathode 12 comprises embodiment fuse element assembly. a first side 15 along the fuse-link 16, and comprises a second

FIG. 9 is a diagrammatic top view of the example side 17 in opposing relation to the first side. The slit 18 embodiment fuse element assembly of FIG. 8 incorporated extends into the cathode 12 from the second side 17.

FIG. 10 diagrammatically illustrates an example pulse 65 sequence that may be utilized relative to the circuit assembly sequence that may be utilized relative to the circuit assembly to the cathode through a narrow neck region. During opera-
of FIG. 9 to rupture a fuse-link of the fuse element assembly. tion of the fuse element, current den

FUSE ELEMENT ASSEMBLIES FIG. 11 is a diagrammatic top view of the example embodiment fuse element assembly of FIG. 8 incorporated into another example embodiment circuit assembly.

FIG. 12 diagrammatically illustrates an example pulse This patent resulted from a continuation of U.S. patent $\frac{5}{5}$ sequence that may be utilized relative to the circuit assembly plication Ser. No. 14/847.235, which was filed Sep. 8. of FIG. 11 to rupture a fuse-link of

FIG. 13 is a diagrammatic top view of the example TECHNICAL FIELD embodiment fuse element assembly of FIG. 8 incorporated 10 into another example embodiment circuit assembly.
FIG. 14 diagrammatically illustrates an example pulse

sequence that may be utilized relative to the circuit assembly BACKGROUND of FIG. 13 to rupture a fuse-link of the fuse element assembly.

E-fuses may be incorporated into integrated circuitry, and 15 FIG. 15 is a diagrammatic top view of the example 15 example 15 embodiment fuse element assembly of FIG. 8 incorporated

Problems may occur during operation of E-fuses in that sequence that may be utilized relative to the circuit assembly
material from the fuse-link accumulates at the cathode as the 30 of FIG. 19 to rupture a fuse-link of th

In some embodiments, the invention includes new fuse BRIEF DESCRIPTION OF THE DRAWINGS element (e.g., E-fuse) configurations which are designed to more uniformly spread accumulating material across a cathode as compared to conventional fuse element configura-FIG. 1 is a diagrammatic top view of an example embodi-

40 tions. The improved spreading of the accumulating material

FIG. 2 is a diagrammatic top view of the example may reduce a thickness of the accumulating material a may reduce a thickness of the accumulating material as compared to conventional fuse element configurations. Such Into an example embodiment circuit assembly.
FIG. 3A is a diagrammatic cross-sectional side view along ate or prevent undesired effects of the accumulating material FIG. 3A is a diagrammatic cross-sectional side view along ate or prevent undesired effects of the accumulating material
the line 3A-3A of FIG. 2. 45 on structures adjacent the E-fuse as compared to convene line 3A-3A of FIG. 2. 45 on structures adjacent the E-fuse as compared to conventriate elements of the E-fuse as compared to conventriate cross-sectional side view along tional fuse element configurations. For instance, FIG. 3B is a diagrammatic cross-sectional side view along tional fuse element configurations. For instance, cracking the line 3B-3B of FIG. 2. FIG. 4 diagrammatically illustrates an example pulse Example embodiments are described with reference to

sequence that may be utilized relative to the circuit assembly anode 14, and a fuse-link 16 between the cathode and the of FIG. 2 to rupture a fuse-link of the fuse element assembly. anode. In some embodiments, the fuse-li FIG. 2 to rupture a fuse-link of the fuse element assembly. anode. In some embodiments, the fuse-link may be consid-
FIG. 6 is a diagrammatic top view of another example ered an example of a first portion of the fuse eleme FIG. 6 is a diagrammatic top view of another example ered an example of a first portion of the fuse element embodiment fuse element assembly incorporated into 55 configuration 10, the cathode may be considered an example example embodiment circuit assembly incorporated into 55 configuration 10 assembly in the cathode may be considered an example $\frac{1}{2}$. The state of a second portion, and the anode may be considered an example of a thir example of a third portion. Unlike a conventional fuse

a first side 15 along the fuse-link 16, and comprises a second FIG. 9 is a diagrammatic top view of the example side 17 in opposing relation to the first side. The slit 18

into an example embodiment circuit assembly.

FIG. 10 diagrammatically illustrates an example pulse 65 the anode 14 to the cathode 12 so that the fuse-link couples tion of the fuse element, current density in the narrow neck

region of the fuse-link may be higher than in wider regions accumulating in two or more locations. Accordingly, the of the fuse-link more distal from the cathode. Such may illustrated embodiment of FIG. 2 may reduce an ove of the fuse-link more distal from the cathode. Such may illustrated embodiment of FIG. 2 may reduce an overall advantageously cause rupture of a fuse-link formed in height of the accumulating material on cathode 12 during advantageously cause rupture of a fuse-link formed in height of the accumulating material on cathode 12 during accordance with the illustrated embodiment to reproducibly fuse-rupture as compared to conventional fuse elemen accordance with the illustrated embodiment to reproducibly fuse-rupture as compared to conventional fuse element occur in the region near the cathode rather than in regions $\frac{1}{2}$ assemblies. Such reduced overall height occur in the region near the cathode rather than in regions 5 assemblies. Such reduced overall height may lead to reduced more distal from the cathode, which may improve reliability stresses on structures adjacent the fils more distal from the cathode, which may improve reliability
and performance of the example embodiment fuse element
as compared to conventional configurations. The current
density across the narrow neck region of the fuse-l build-up of current concentration at the interface of the transferred material.
fuse-link and anode. $\frac{15}{2}$ FIGS. 3A and 3B sho

symmetry along a plane 19 which bifurcates the fuse ele-

which extend along opposing sides of the fuse-link 16. The 20 insulative material 42, which projections 20 and 22 are spaced from the fuse-link by gaps semiconductor substrate 44. 24 and 26. In some embodiments, the illustrated fuse-link The insulative material 42 may comprise any suitable may be considered to have a relatively wide region adjacent composition or combination of compositions, includi may be considered to have a relatively wide region adjacent composition or combination of compositions, including, for anode 14, and a relatively narrow region adjacent cathode example, one or more of silicon dioxide, sili 12, and the illustrated projections 20 and 22 may be con- 25 borophosphosilicate glass, fluorosilicate glass, etc.
sidered to extend along opposing sides of the relatively The semiconductor substrate 44 may comprise any su

different wirings M1, M2 and M3 (which may be considered 30 to comprise three separate electrodes in some embodito comprise three separate electrodes in some embodi-
members in the limited to, bulk semiconductive materials such
members). The wirings M1 and M2 are coupled to the cathode
as a semiconductive wafer (either alone or in a 12 through contacts 31 and 33, respectively; and the wiring $M3$ is coupled to the anode through contacts 35. The illustrated contacts are example configurations, and the total 35 number of contacts, locations of the contacts, and sizes of ture, including, but not limited to, the semiconductor subcontacts may vary in other embodiments. The wirings may strates described above. comprise any suitable conductive material (for example, The cathode 12 may comprise any suitable material, and some embodiments may comprise one or more of conductive material.

considered to comprise a first region 32 comprising projec-
tions 20 and 22, and a second region 34 offset from the first metal-containing composition (for instance, metal silicide) region. The wiring $M2$ may be considered to be first wiring connected to the first region 32 of the cathode, and the wiring M1 may be considered to be second wiring connected 45 to the second region 34 of the cathode. The first and second to the second region 34 of the cathode. The first and second ($FIG. 2$) may comprise the same composition as the cathode wirings may be configured to be operated independently of 12 in some embodiments; and in other embodim wirings may be configured to be operated independently of 12 in some embodiments; and in other embodiments one or
one another for providing a pulse train to impart rupture of both of the anode and fuse-link may comprise a

The slit 18 within the assembly 30 of FIG. 2 may be utilized for rupturing fuse-link 16 and causing electromiconsidered to be an example of a control element that gration of material from the rupture-region 36 of the fuseconsidered to be an example of a control element that gration of material from the rupture-region 36 of the fuse-
modifies flow of transferred material during rupture of the link to the accumulation regions 38 and 40 of th fuse-link 16, and which directs the transferred material along The pulse sequence includes a set of pulses 46 imparted to two or more paths across the cathode to reduce an overall 55 wiring M1, a set of pulses 48 imparted two or more paths across the cathode to reduce an overall 55 wiring M1, a set of pulses 48 imparted to wiring M2; and height of the material accumulating on the cathode. For ground (GND), or other suitable static condition height of the material accumulating on the cathode. For ground (GND), or other suitable static condition, at wiring instance, during operation of assembly 30 the fuse-link 16 M3. The pulses 46 and 48 establish a pulse trai instance, during operation of assembly 30 the fuse-link 16 M3. The pulses 46 and 48 establish a pulse train. When the may be ruptured within an illustrated rupture-region 36 due voltage at wiring M1 is at a high level at t may be ruptured within an illustrated rupture-region 36 due voltage at wiring M1 is at a high level at time t1, migration to electromigration of material from such rupture-region to proceeds between the wiring M1 and the f the cathode 12. The slit 18 may disperse flow of the 60 electromigrating material along two paths so that the mateelectromigrating material along two paths so that the mate-

proceeds between the wiring $\overline{M2}$ and the fuse-link 16. The

proceeds between the wiring $\overline{M2}$ and the fuse-link 16. The

proceeds between the wiring $\$ fuse element assemblies lack a control element to modify (for instance, to achieve a short OFF period of current in the flow of transferred material along the cathode, and thus fuse-link). Utilization of two pulses may ena flow of transferred material along the cathode, and thus fuse-link). Utilization of two pulses may enable the cathode transferred material accumulates in a single location. A 65 12 to cool between pulses, while keeping volume of material accumulating in a single location will Such may enable rupture to be induced within the fuse-link
form a higher mound as compared to a same volume without overheating the cathode. form a higher mound as compared to a same volume

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FIGS. 3A and 3B show cross-sections along the cathode 12 of fuse element assembly 30 in crossing directions, and The illustrated fuse element configuration 10 has mirror 12 of fuse element assembly 30 in crossing directions, and
mmetry along a plane 19 which bifurcates the fuse ele-
show the accumulation regions 38 and 40 laterally s ment into two halves.
The cathode 12 comprises a pair of projections 20 and 22 3B also show that the cathode 12 may be formed over an The cathode 12 comprises a pair of projections 20 and 22 3B also show that the cathode 12 may be formed over an inch extend along opposing sides of the fuse-link 16. The $_{20}$ insulative material 42, which in turn is for

narrow region.

FIG. 2 shows the fuse element 10 incorporated into an prise, consist essentially of, or consist of monocrystalline FIG. 2 shows the fuse element 10 incorporated into an prise, consist essentially of, or consist of monocrystalline assembly 30 (i.e., a fuse element assembly) comprising three silicon. The term "semiconductor substrate" me silicon. The term "semiconductor substrate" means any construction comprising semiconductive material, includas a semiconductive wafer (either alone or in assemblies comprising other materials), and semiconductive material layers (either alone or in assemblies comprising other materials). The term "substrate" refers to any supporting struc-

ngsten, etc.).
In the illustrated embodiment, the cathode 12 may be 40 tively-doped silicon, metal, etc. For instance, in some In the illustrated embodiment, the cathode 12 may be 40 tively-doped silicon, metal, etc. For instance, in some considered to comprise a first region 32 comprising projec-
embodiments the cathode may comprise a layer of me metal-containing composition (for instance, metal silicide) over a layer of conductively-doped silicon; in some embodiments the cathode may comprise only metal or metal-containing material; etc. The anode 14 and fuse-link 16 both of the anode and fuse-link may comprise a different

the fuse-link 16, as described in more detail below with composition than the cathode.

FIG. 4 shows an example pulse sequence that may be

The slit 18 within the assembly 30 of FIG. 2 may be

utilized for rupturing fuse-l proceeds between the wiring M1 and the fuse-link 16; and when the wiring M2 is at the high level at time t_2 , migration

numerous other sequences may be utilized in other embodi-
ments. For instance, FIG. 5 shows another example pulse in contact with cathode 12, and to comprise wiring M8 in ments. For instance, FIG. 5 shows another example pulse in contact with cathode 12, and to comprise wiring M8 in sequence. The sequence of FIG. 5 includes high-level pulses contact with anode 14. The wiring M8 may be analo sequence. The sequence of FIG. 5 includes high-level pulses on both of wirings M1 and M2 at time t3 which may induce $\frac{5}{10}$ the wiring M3 described above with reference to FIG. 2. The electromigration of material across an entirety of cathode 12. wirings M4, M5, M6 and M7 may be considered to comprise
Some example operating conditions may include:
first and second wirings (for instance M4 and M7) analog

In some emoduments, a degree of overlap voltages
between wirings M1 and M2 may be designed as an analog
triangular waveform rather than as a digital rectangular
waveform. Some example operating conditions may
into the larg

The fuse element 10 of FIGS. 1-5 includes a fuse-link 16 concentration points of current density to be dispersed having a uniform taper from anode 14 to cathode 12. In other amongst four different times and places. FIG. 10 order to achieve the desired relatively narrow region adja-25 embodiment of FIG. 9 (the wiring M8 is not shown in FIG. cent cathode 12 and relatively wide region adjacent anode 10, and may be maintained at an electrical gr 14. For instance, FIG. 6 shows an assembly 30*a* having a suitable static condition). The additional wirings of FIG. 9 fuse element 10*a* in which the fuse-link 16*a* is triangle-
relative to those of FIG. 2, and the asso fuse element $10a$ in which the fuse-link $16a$ is triangle-
shaped in a region 50 adjacent the anode 14 .
pulses that may be interspersed utilizing such additional

to light-interference and/or other problems that may mani-
fuse-link; and specifically may enable such rupture to be
fest during the patterning of such desired shape. FIG. 7 achieved with better cooling of the cathode and fest during the patterning of such desired shape. FIG. 7 achieved with better cooling of the cathode and an acceler-
illustrates a potential solution to such fabrication difficulties. ated rate of rupture. illustrates a potential solution to such fabrication difficulties. ated rate of rupture.
Specifically, FIG. 7 shows an assembly $30b$ having dummy 35 The wirings associated with cathode 12 of FIGS. 2 and 9 elements 52 a elements 52 and 54 provided adjacent the fuse-link 16 to span continuously across an entire width dimension of the assist during fabrication of such fuse-link. The elements are cathode. For instance, FIG. 9 shows the catho assist during fabrication of such fuse-link. The elements are cathode. For instance, FIG. 9 shows the cathode having a referred to as "dummy" elements to indicate that they have width dimension D, and shows the wirings M4, referred to as "dummy" elements to indicate that they have width dimension D, and shows the wirings M4, M5, M6 and no function in the integrated circuit, but rather are provided M7 all spanning continuously across the enti solely to assist during the patterning of fuse element 10. The 40 dummy elements may comprise any suitable composition or vided in segments which span only a portion of the width combination of compositions, including, for example silicon dimension of the cathode. For instance, FIG. 11 s combination of compositions, including, for example silicon dimension of the cathode. For instance, FIG. 11 shows an dioxide, silicon nitride, silicon, metal, etc. Although the assembly 30d comprising wirings M9, M10, M11, illustrated elements 52 and 54 are described as dummy M13, M14, M15 and M16 coupled with the cathode 12, with elements; in other embodiments one or both of the elements 45 each of such wirings being a segment which spans o elements; in other embodiments one or both of the elements 45 52 and 54 may be a circuit element rather than a dummy 52 and 54 may be a circuit element rather than a dummy portion of the width dimension D of the cathode. The element.

comprises a pair of opposing sidewalls 51 and 53 that extend M3 described above with reference to FIG. 2. The wirings from anode 14 to cathode 12. Such sidewalls may be $50 \text{ M}9$, M10, M11, M12, M13, M14, M15 and M16 may from anode 14 to cathode 12. Such sidewalls may be 50 M9, M10, M11, M12, M13, M14, M15 and M16 may be referred to as a first sidewall and a second sidewall, respec-
considered to comprise first, second, third, fourth, etc. tively. The dummy features 52 and 54 may be referred to as wirings. Utilization of multiple wirings coupled with the first and second dummy features that are along the first and cathode may enable the pulse train utilized first and second dummy features that are along the first and cathode may enable the pulse train utilized for rupturing the second sidewalls, respectively. The first dummy feature 52 fise-link to be tailored for particular second sidewalls, respectively. The first dummy feature 52 fuse-link to be tailored for particular applications, analo-
is spaced from the first sidewall 51 by a first gap 56, and the 55 gously to advantages discussed abov second dummy feature 54 is spaced from the second side-
wall 53 by a second gap 58. The embodiment of FIG. 7 has FIG. 12 illustrates an example pulse sequence that may be the gap 24 between projection 20 and fuse-link 16, and has utilized with the embodiment of FIG. 11. The eight wirings the gap 26 between projection 22 and the fuse-link 16. The $(M9-M16)$ associated with the cathode may enab

gaps 24 and 26 may be referred to as third and fourth gaps. 60
The fuse element 10 of FIG. 1 is an example configuration, and other configurations may be utilized in other wiring M17 may be maintained at electrical ground, or other embodiments. For instance, FIG. $\bf{8}$ shows a fuse element $\bf{10}b$ suitable static condition, during having a slightly different configuration than the fuse ele-
The embodiments of FIGS. 2, 4, 5, 6, 7, 9 and 11 utilize
ment 10 of FIG. 1. The fuse element 10b is used in 65 wirings which divide electron current/migration l ment 10 of FIG. 1. The fuse element $10b$ is used in 65 describing example embodiments shown in FIGS. 9, 11, 13 describing example embodiments shown in FIGS. 9, 11, 13 view of a time-divided manner initiated by a pulse train.
FIG. 13 illustrates an alternative fuse element assembly

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The pulse sequence of FIG. 4 is an example sequence, and Referring to FIG. 9, an assembly $30c$ is shown to commercies may be utilized in other embodi-
mercius other sequences may be utilized in other embodi-Some example operating conditions may include:

me example operating conditions may include:

first and second wirings (for instance M4 and M7) analogous

to the wirings M1 and M2 of FIG. 2, and to further comprise

to the M1:3V, M2:0V—migration direction: M1
M1:3V, M2:0V—migration direction: M1
M1:0V, M2:3V—migration direction: M2
M1:0V, M2:3V—migration direction: M2
M1:0V, M2:3V —migration direction: intermediate 10 multiple wirings coupl M1:3V, M2:3V—migration direction: intermediate $\frac{10}{2}$ multiple wirings coupled with the cathode may enable the between M1 and M2 $\frac{1}{2}$ between M1 and M2 pulse train utilizing a larger
In some embodiments, a degree of overlap voltages and punk to a context with the extends is that the M1:3V, M2:1V—migration direction: between M1 and
M2, closer to M1
M1:1V, M2:3V—migration direction: between M1 and 20
M5, M6 and M7) associated with the cathode may enable
M2, closer to M2
M3. N6 and M7) associated with th

an example pulse sequence that may be utilized with the pulses that may be interspersed utilizing such additional In some embodiments it is recognized that it may be 30 wirings, may enable better control of assembly $30c$ of FIG.
difficult to fabricate a fuse-link having a desired shape due
to the assembly 30 of FIG. 2 during rupture

M7 all spanning continuously across the entirety of such width dimension. In other embodiments, wirings are proelement.

In the shown embodiment of FIG. 7, the fuse-link 16 anode 14. The wiring M17 may be analogous to the wiring In the wiring anode 14. The wiring M17 may be analogous to the wiring M3 described above with reference to FIG. 2. The wirings

 $(M9-M16)$ associated with the cathode may enable concentration points of current density to be dispersed amongst The fuse element 10 of FIG. 1 is an example configura-
tion, and other configurations may be utilized in other wiring M17 may be maintained at electrical ground, or other

FIG. 13 illustrates an alternative fuse element assembly

wherein wiring is configured to divide electron current later and 40 (i.e., directs accumulating material into two migration longitudinally in the view of a time-divided and 40 (i.e., directs the accumulating material into manner initiated by a pulse train. Specifically, FIG. 13 shows paths, one of which leads to location 38 and the other of a fuse element assembly 30e having wirings M18 and M19 which leads to location 40). extending longitudinally along cathode 12. Alternatively 5 The hole 64 of FIG. 17, and slits 18 of FIGS. 1 and 8, are considered, the cathode 12 may be considered to comprise examples of static control elements (i.e., cont considered, the cathode 12 may be considered to comprise examples of static control elements (i.e., control elements mirror symmetry along the plane 19. The plane 19 bifurcates which remain the same in all operational phas mirror symmetry along the plane 19. The plane 19 bifurcates which remain the same in all operational phases of the fuse the cathode into a first half 60 comprising projection 22, and elements). Another type of control elem a second half 62 comprising projection 20. The first wiring utilized in some embodiments is a non-static control ele-
M18 is electrically connected to the first half 60, and the 10 ment, such as, for example, a control ele M18 is electrically connected to the first half 60, and the 10 ment, such as, for example, a control element which is second wiring M19 is electrically connected to the second charged in some operational states of the fuse half 62. The first and second wirings may be configured to 18 shows a fuse element $10d$ comprising an electrically be operated independently one another for providing a pulse conductive contact 66 incorporated into a c train to impart rupture of fuse-link 16 within the rupture-
region 36. Since four contacts are located between each of 15 contact during operation of the fuse element. the wirings $M18$ and $M19$ and the cathode, the electron FIG. 19 shows the fuse element $10d$ incorporated into a current/migration under each of the wirings may expand into fuse element assembly $30h$ comprising wirings current/migration under each of the wirings may expand into fuse element assembly $30h$ comprising wirings M23, M24 a fan-shape during rupture of the fuse-link. The assembly and M25. The wiring M23 is coupled with cathode a fan-shape during rupture of the fuse-link. The assembly and M25. The wiring M23 is coupled with cathode 12 and 30e also comprises a third wiring M20 coupled with the the wiring M25 is coupled with anode 14. The wiring M anode 14. Such third wiring may be maintained at ground, 20 is coupled with the electrically conductive contact 66 , and or other suitable static condition, during rupture of the may be utilized to impart electrical curr or other suitable static condition, during rupture of the may be utilized to impart electrical current and/or potential fuse-link.

voltage may be alternately applied to each of the wirings 25 M18 an M19 to allow electron current to flow therethrough. position or combination of compositions; and may, for The utilization of the illustrated wiring configuration may example, comprise one or both of silicon nitride The utilization of the illustrated wiring configuration may example, comprise one or both of silicon nitride and silicon enable the cathode to remain cool during rupture of a dioxide. fuse-link even though the electron current may flow through In operation, an electrically-altered region 70 may be the fuse-link for substantial duration so that the fuse-link 30 formed around contact 66 utilizing electrical potential and/or may stay hot. Specifically, current is pulsed alternately on current flow generated with wiring M24. In some embodi-
opposing halves of the cathode to enable each half to ments, the contact 66 (specifically, the electrical opposing halves of the cathode to enable each half to ments, the contact 66 (specifically, the electrically-altered alternately heat and cool, and yet the current remains rela-
region 70) may redirect accumulating material alternately heat and cool, and yet the current remains rela-
tively steady on the fuse-link to keep the fuse-link hot.
38 and 40 (i.e., directs the accumulating material into two

another example embodiment. Specifically, a single wiring which leads to location 40). In some embodiments, the M21 extends across the entirety of cathode 12, and another contact 66 may be electrically floating. In some em wiring M22 extends across anode 14. It may be simpler to fabricate the embodiment of FIG. 15 having only two fabricate the embodiment of FIG. 15 having only two polarity (i.e., reverse relation) to that utilized to induce wirings, as compared to some of the other embodiments 40 rupture of fuse-link 16, and such opposite polarity wirings, as compared to some of the other embodiments 40 rupture of fuse-link 16, and such opposite polarity may described herein which comprise multiple wirings. The redirect accumulating material along two or more paths described herein which comprise multiple wirings. The redirect accumulating material along two or more paths to embodiment of FIG. 15 may be useful in applications in reduce a height of the accumulating material (i.e., to embodiment of FIG. 15 may be useful in applications in reduce a height of the accumulating material (i.e., to flatten which a relatively simple pulse train may be utilized to the accumulating material). FIG. 20 illustrates which a relatively simple pulse train may be utilized to the accumulating material). FIG. 20 illustrates a pulse rupture fuse-link 16 while maintaining desired performance sequence which may be utilized relative to wirings rupture fuse-link 16 while maintaining desired performance sequence which may be utilized relative to wirings M23 and characteristics. 45 M24 to induce a reverse flow of electrons within the region

element $10b$ of FIG. **8** is an example control element which the general flow of the electrons utilized to rupture the may be utilized to modify flow of transferred material along fuse-link **16**. The overall influence of a cathode during fuse rupture. FIG. 16 shows a fuse element contact 66 on the migration of accumulating material may be $10c$ having a different configuration; and specifically shows 50 tailored by modifying the amplitu 10c having a different configuration; and specifically shows 50 tailored by modifying the amplitude, duration and/or overall a control element corresponding to a hole 64 extending shape of pulses provided at the contact 66 through the cathode 12. The hole may have any suitable
shape; and may, for example, be elliptical, circular, home-
based-shaped, rectangular, polygonal, square, etc. The hole
is entirely laterally surrounded by conductive cathode 12. The hole may be filled with solid or semisolid leading to region 40) utilizing the illustrated control ele-
insulative material (e.g., silicon dioxide, silicon nitride, ments, in other embodiments control eleme insulative material (e.g., silicon dioxide, silicon nitride, ments, in other embodiments control elements may be configured to direct accumulating material along more than

fuse element assembly $30g$ comprising wirings M21 and 60 The fuse elements and fuse element assemblies discussed M22 of the type described above with reference to FIG. 15. above may be utilized in electronic systems. Suc M22 of the type described above with reference to FIG. 15. above may be utilized in electronic systems. Such electronic In other embodiments, other wiring configurations may be systems may be used in, for example, memory m utilized, including, for example, any of the other wiring device drivers, power modules, communication modems, configurations described above with reference to FIGS. 2 processor modules, and application-specific modules, a and $4\n-14$. The hole 64 may be placed in a location where 65 transferred material from fuse-link 16 would accumulate in

and 40 (i.e., directs the accumulating material into two

elements). Another type of control element which may be

the wiring M25 is coupled with anode 14. The wiring M24 se-link.
FIG. 14 illustrates an example pulse sequence that may be **12**. In the illustrated embodiment, the wiring M24 is elec-FIG. 14 illustrates an example pulse sequence that may be 12. In the illustrated embodiment, the wiring M24 is electrilized with the embodiment of FIG. 13. A high-level trically isolated from the wiring M23 by an insulativ trically isolated from the wiring M23 by an insulative region 68. Such insulative region may comprise any suitable com-

the fuse-link to keep the fuse-link hot . 38 and 40 (i.e., directs the accumulating material into two FIG. 15 illustrates a fuse element assembly 30 fillustrating 35 paths, one of which leads to location 38 and the other o paths, one of which leads to location 38 and the other of contact 66 may be electrically floating. In some embodi-
ments, the contact 66 may have a voltage of opposite The slit 18 of the fuse element 10 of FIG. 1 and the fuse $\frac{70}{1}$ (i.e., a region proximate the contact 66) as compared to element 10 of FIG. 8 is an example control element which the general flow of the electrons util fuse-link 16. The overall influence of electrical flow along contact 66 on the migration of accumulating material may be

etcomponent to direct accumulating material along more than FIG. 17 shows the fuse element $10c$ incorporated into a two paths.

transferred material from fuse-link 16 would accumulate in systems may be any of a broad range of systems, such as, for the absence of such hole. In the illustrated embodiment, the example, cameras, wireless devices, displ example, cameras, wireless devices, displays, chip sets, set

top boxes, games, lighting, vehicles, clocks, televisions, cell
phones, personal computers, automobiles, industrial control
states of the fuse link.
of the fuse link.

The particular orientation of the various embodiments in 2. The fuse element assembly of claim 1, wherein the first the drawings is for illustrative purposes only, and the $\frac{5}{2}$ portion of the cathode, and the third p the drawings is for illustrative purposes only, and the $\frac{1}{2}$ portion of the cathode, and the third projecting portion of the embodiments may be rotated relative to the shown orienta-
cathode are different in width fr embodiments may be rotated relative to the shown orienta-
tions in some applications. The description provided herein,
and the claims that follow, pertain to any structures that have
the described relationships between var

sections, and do not show materials behind the planes of the portion of the cathode is wider than the fourth projecting cross-sections in order to simplify the drawings.

configured to be ruptured as materials of the first portion portion of the cathode are equal in width to each other, and flow to a second portion (e.g., 12) through electromigration. the third projecting portion of the cat flow to a second portion (e.g., 12) through electromigration. The second portion is configured to accumulate the materials 20 projecting portion of the cathode are equal in width to each that have flowed from the first portion. The assembly other. includes a control element (e.g., slit **18**, hole **64**, contact **66** $\qquad 5$. The fuse element assembly of claim 1, wherein the fuse configured to divide the flow of materials into at least two link has a relatively narro

(e.g., 30, 30*a-h*) comprising an anode (e.g., 14), a cathode $\overline{6}$. A fuse element assembly comprising: (e.g., 12), a fuse-link (e.g., 16, 16*a*) between the anode and $\overline{6}$ a first cathode projection extending in

(e.g., $\overline{12}$), and a rise-link (e.g., $\overline{16}$, \over during transfer of material from the fuse-link into the a third cathode projection branching from the first cathode cathode The fuse-link has a relatively narrow region adia-

projection, at least a portion of the third ca cathode. The fuse-link has a relatively narrow region adja projection, at least a portion of the third cathode
cent the cathode and a relatively wide region adjacent the projection extending in a direction opposite to the cent the cathode and a relatively wide region adjacent the projection extending in a direction opposite to the first continuous can direction opposite to the first extending in a direction opposite to the first extending anode. The cathode has a pair of projections (e.g., 20, 22) cathode projection;
that extend along opposing sides of the relatively narrow 40 a fourth cathode projection branching from the second that extend along opposing sides of the relatively narrow 40 a fourth cathode projection branching from the second
region and that are spaced from the relatively narrow region region and that are spaced from the relatively narrow region
by gaps (e.g., 24, 26). The assembly includes a control
element (e.g., slit 18, hole 64, contact 66) which modifies fourth cathode projections having a second of element (e.g., slit 18, hole 64, contact 66) which modifies fourth cathode projections having flow of the transferred material along the cathode and which ebetween in the second direction.

In compliance with the statute with the statute with the statute of the statute matter discussed than to the subject is specific as to structural and methodical features. It is to be $\frac{1}{2}$ a first electrode configured specific as to structural and methodical features. It is to be a first electrode configured to the supplied with a supplied with a supplied to the supplied with a supplied with a supplied with a supplied with a supplied wi understood, however, that the claims are not limited to the voltage;
specific features shown and described, since the means 50 a second electrode; specific features shown and described, since the means 50 a second electrode; herein disclosed comprise example embodiments. The a third electrode; and herein disclosed comprise example embodiments. The a third electrode; and
claims are thus to be afforded full scope as literally worded, a fuse element assembly including a first region coupled and to be appropriately interpreted in accordance with the to the first electrode, a second region coupled to the doctrine of equivalents.

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- a cathode having a first end and an opposing second end; jection being independently connected to the first election, the first and second projecting portions being substantially parallel to each other and merging at a
- a fuse link extending from the merge region and beyond between, the second region and the third region.
the second end of the cathode; and further comprising 65 9. The apparatus of claim 8, wherein the first and second the second end of the cathode; and further comprising 65 a third projecting portion of the cathode and a fourth
- projecting portion of the cathode, the third and fourth

Some embodiments include a fuse element assembly $(1, 3, 30, 30a-h)$ comprising a first portion $(e.g., 16, 16a)$ projecting portion of the cathode and the second projecting

paths along the second portion. The flow of materials include a relatively narrow portion further away from the membodiments include a fuse element assembly 25 merge region.

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- (e.g., 12), a fuse-fink (e.g., 10, 10*a*) between the anode and
the cathode projection extending in a first direction;
the cathode and configured to rupture during transfer of
material from the fuse-link into the cathode,
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disperses said flow along at least two paths. 45 7. The fuse element assembly of claim 6, wherein the first In compliance with the statute, the subject matter dis-
In compliance with the statute, the subject matter dis-
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- second electrode and a third region coupled to the third electrode, the fuse element assembly having a cathode I claim:

1. A fuse element assembly comprising:

1. A fuse element assembly comprising:

1. A fuse element assembly comprising:

1. A fuse element assembly comprising: end being divided into two projections with each prothe cathode having a slit into the first end that spaces a trode; the cathode further having a second end having first projecting portion from a second projecting por- 60 two projections that independently connect to the s two projections that independently connect to the second electrode; the fuse element assembly further comprising an anode comprising the third region and conmerge region; and
fuse link extending from the merge region and beyond
between, the second region and the third region.

electrodes are configured to be operated independently relative to one another.

10. The apparatus of claim 9, further comprising first, second and third contacts provided on the first, second and unia electrodes, respectively.

* * * * *